

Title (en)
Apparatus for thin film growth

Title (de)
Vorrichtung zum Wachstum einer dünnen Schicht

Title (fr)
Appareillage de croissance d'une couche mince

Publication
EP 0953659 A3 20030917 (EN)

Application
EP 99108282 A 19990427

Priority
JP 13438298 A 19980428

Abstract (en)
[origin: EP0953659A2] In an apparatus for vapor phase growth of silicon single crystal thin films, in-plane uniformity of susceptor temperature is improved and film thickness of a silicon single crystal thin film is uniformized. The base material of a lift pin 8 provided in a pocket 5a of a susceptor 5 is changed to a base material lower in thermal conductivity than a base material of the susceptor 5, by which local decreases in susceptor temperature in the vicinity of the lift pin are prevented. As the base material of the lift pin 8, SiC, carbon of a desired grade and quartz are preferred.
<IMAGE>

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IPC 8 full level
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CPC (source: EP US)
C23C 16/4581 (2013.01 - EP US); **C23C 16/46** (2013.01 - EP US); **C30B 25/10** (2013.01 - EP US); **C30B 25/12** (2013.01 - EP US); **C30B 29/06** (2013.01 - EP US); **H01L 21/67103** (2013.01 - EP US); **Y10T 117/10** (2015.01 - EP US)

Citation (search report)
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